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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/765,673	01/26/2004	Doron Meshulach	8935 USA/PDC/PDC	9888
DATENT COL	7590 06/14/2007		EXAMINER	
PATENT COUNSEL APPLIED MATERIALS, INC.			SULLIVAN, CALEEN O	
Legal Affairs D P.O. Box 450A	_		ART UNIT	PAPER NUMBER
Santa Clara, CA	A 95052		1756	
			MAIL DATE	DELIVERY MODE
			06/14/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

	Application No.	Applicant(s)
	10/765,673	MESHULACH, DORON
Office Action Summary	Examiner	Art Unit
	Caleen O. Sullivan	1756
The MAILING DATE of this communicatio Period for Reply	n appears on the cover sheet wi	th the correspondence address
A SHORTENED STATUTORY PERIOD FOR R WHICHEVER IS LONGER, FROM THE MAILIN - Extensions of time may be available under the provisions of 37 C after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory in the set or extended period for reply will, by any reply received by the Office later than three months after the earned patent term adjustment. See 37 CFR 1.704(b).	NG DATE OF THIS COMMUNIC SFR 1.136(a). In no event, however, may a re on. period will apply and will expire SIX (6) MON statute, cause the application to become AB.	CATION. poly be timely filed THS from the mailing date of this communication. ANDONED (35 U.S.C. § 133).
Status	·	
 Responsive to communication(s) filed on This action is FINAL. Since this application is in condition for al closed in accordance with the practice un 	This action is non-final. Iowance except for formal matte	•
Disposition of Claims	·	
4) Claim(s) 1-18 is/are pending in the applic 4a) Of the above claim(s) 10-18 is/are with 5) Claim(s) is/are allowed. 6) Claim(s) 1-9 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction a	ndrawn from consideration.	
Application Papers		•
9) ☐ The specification is objected to by the Exa 10) ☑ The drawing(s) filed on 26 January 2004 is Applicant may not request that any objection to Replacement drawing sheet(s) including the control of	s/are: a) \square accepted or b) \square of the drawing(s) be held in abeyan orrection is required if the drawing(ce. See 37 CFR 1.85(a). s) is objected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
 12) Acknowledgment is made of a claim for fo a) All b) Some * c) None of: 1. Certified copies of the priority docu 2. Certified copies of the priority docu 3. Copies of the certified copies of the application from the International B * See the attached detailed Office action for 	ments have been received. ments have been received in Ap e priority documents have been ureau (PCT Rule 17.2(a)).	oplication No received in this National Stage
Attachment(s) 1)		ummary (PTO-413)
 Notice of Draftsperson's Patent Drawing Review (PTO-94 Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date <u>06/29/2005</u>. 	8) Paper No(s)/Mail Date formal Patent Application

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DETAILED ACTION

Election/Restrictions

- 1. Restriction to one of the following inventions is required under 35 U.S.C. 121:
 - I. Claims 1-9, drawn to a method of printing a pattern, classified in class 430, subclass311.
 - II. Claims 10-18, drawn to a system for printing a pattern, classified in class 355, subclass 69.

The inventions are distinct, each from the other because of the following reasons:

- 2. Inventions I and II are related as process and apparatus for its practice. The inventions are distinct if it can be shown that either: (1) the process as claimed can be practiced by another and materially different apparatus or by hand, or (2) the apparatus as claimed can be used to practice another and materially different process. (MPEP § 806.05(e)). In this case the apparatus as claimed can be used to practice another and materially different process such a method of forming an image by laser microscopy.
- 3. Because these inventions are independent or distinct for the reasons given above and there would be a serious burden on the examiner if restriction is not required because the inventions have acquired a separate status in the art due to their recognized divergent subject matter, restriction for examination purposes as indicated is proper.
- 4. During a telephone conversation with Attorney Tarek N. Fahmi on 05/31/2007 a provisional election was made with traverse to prosecute the invention of Group I, claims 1-9. Affirmation of this election must be made by applicant in replying to this Office action. Claims 10-18 are withdrawn from further consideration by the examiner, 37 CFR 1.142(b), as being drawn to a non-elected invention.

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Claim Rejections - 35 USC § 102

5. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 6. Claims 1 and 4 are rejected under 35 U.S.C. 102(b) as being anticipated by Norimasa.

Norimasa discloses a method of patterning optical recording medium layer that is comprised of a photosensitive material. (See, abstract). Norimasa discloses that an optical recording layer (3) that comprises photosensitive material, a wavelength changing layer (4) that comprises a non-linear optical material, such as beta-barium borate, as well as a light absorbing layer (5) and a protective layer, if necessary, are formed on a supporting substrate (2). (See, abstract). The nonlinear optical material induces the second or third nonlinear polarization on the inside therein to emit light having a wavelength that is ½ or 1/3 that of the incident light. (See, abstract).

Norimasa also discloses that the optical absorption layer contains the wavelength band of the photosensitive material, which comprises the photo-recording layer, in it absorption wavelength band; however, the optical absorption layer does not contain the wavelength band of the incident light. (See, abstract). Norimasa discloses that the method allows the use of laser light, which decreases the cost of reproducing the optical recording medium, which can also be made in a small size. (See, abstract).

Norimasa discloses all the limitations of claims 1 and 4.

Claim Rejections - 35 USC § 103

7. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

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(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

- 8. The factual inquiries set forth in *Graham* v. *John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:
 - 1. Determining the scope and contents of the prior art.
 - 2. Ascertaining the differences between the prior art and the claims at issue.
 - 3. Resolving the level of ordinary skill in the pertinent art.
 - 4. Considering objective evidence present in the application indicating obviousness or nonobviousness.
- 9. Claims 2-3 and 5-9 are rejected under 35 U.S.C. 103(a) as being unpatentable over Norimasa in view of Tsang. Norimasa is relied upon as discussed in the rejection of claims 1 and 4. However Norimasa fails to explicitly disclose the limitations of claim 2, where the at least one beam of radiation is focused onto the intermediate layer and the limitation of claim 3 where the beam of fundamental frequency is substantially located at an interface defined by the medium and the intermediate layer. Norimasa also fails to disclose the limitation of claims 5 where the beam of fundamental frequency is characterized by a short duration or the limitation of claim 6 her the beam of fundamental radiation is characterized by high intensity. Norimasa further fails to disclose the limitation of claim 7, where the fundamental frequency is within the UV or EUV spectral range. Norimasa neither discloses a step where at least two beams of fundamental frequency were directed simultaneously towards at least two locations of the intermediate layer nor does Norimasa disclose that the X⁽³⁾ of the medium differs from the X⁽³⁾ of the intermediate layer. However, Tsang discloses such limitations.

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Tsang discloses optical third-harmonic generation at interfaces. Tsang discloses that when using a focused high-intensity ultra-short lasers pulses, which meets the limitation of claims 5 and 6, normally weak THG process becomes highly operable at a simple air-dielectric interface (See, abstract). In particular, in the experiments discloses, Tsang uses a femto-second laser oscillator that focuses on the interface between two different lossless materials, which meets the limitation of claims 2 and 3, from which a strong THG signal is obtained. (See, pg. 4116). Tsang discloses that this enhancement of the THG signal at the interface of the materials is analogous to the well-known SHG and is highly localized at the interface of the materials. (See, pg. 4116).

Tsang further discloses that high-order harmonic generation at an interface of two different non-absorbing dielectric media using a focused beam is a fundamental physical process and is a universal nonlinear optical property of interfaces. (See, pg. 4116). Tsang also discloses an experiment where third harmonic radiation is generated at an interface of differing materials. In one example Tsang uses a multiple layered system, consisting of multiple dielectric layers. (See, pg. 4123). In particular the layered dielectric mirror consisted of about 13 stacks of high-low index structures made of HfO2 and a SiO2. (See, pg. 4123).

In the example Tsang discloses that a fundamental beam is focused on the dielectric stack and the THG at every interface, of air and the dielectric material, is either transmitted or reflected. (See, pg. 4123). Tsang further discloses that the THG wavelength is 258nm and the fundamental beam has a wavelength of 775nm, which meets the limitation of claim 7. (See, pg. 4123). Tsang also discloses that the X⁽³⁾ of surface of the material layer as compared to X⁽³⁾ of air, is generally 10⁶ larger, which meets the limitation of claim 9. (See, pg. 4124). Tsang also includes example experiments where THG is formed at the interface of air and a material such as beta-barium borate

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crystal, which Norimasa discloses can be used as the wavelength changing material in the process of patterning the photosensitive optical recording medium layer.

It would have been obvious to one of ordinary skill in the art at the time of invention by applicant to modify the teachings of Norimasa with the teachings of Tsang because Tsang discloses that third harmonic radiation is generated at an interface between differing materials, when a fundamental beam is focused on the interface between air, as a medium, and a material layer and this radiation that is generated is propagated through the material layer.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Caleen O. Sullivan whose telephone number is 571-272-6569. The examiner can normally be reached Monday-Friday, 8:30am-5:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on 571-272-1385. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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/COS/, 06/05/07

REARIN F. HUR? SUPERVISORY PATENT EXCLANER